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- 3. (Amended) An apparatus as claimed in claim 2, wherein said temperature control unit and said pressure control unit control a partial pressure of said raw material in said gas phase region by controlling an equilibrium vapor pressure in said gas phase region and said liquid phase region.
- 7. (Amended) An apparatus as claimed in claim 6, further comprising a gas material supply valve that controls a flow rate of said raw material in the gas phase from said tank to said reaction vessel.
- 8. (Amended) An apparatus as claimed in claim 6, further comprising a filter provided between said tank and said gas material supply valve that filters said raw material in the gas phase supplied to said reaction vessel through said gas material supply valve.
- 24. (Amended) A method for manufacturing a glass base material and maintaining the purity of a raw material, comprising:

providing a raw material of said glass base material,

heating said raw material to vaporize said raw material and generate a raw material in the gas phase,

supplying a carrier gas to reduce the partial pressure of said raw material in the gas phase to vaporize said raw material,

controlling a temperature of said raw material to be constant by adjusting said heating of said raw material, and

controlling said partial pressure of said raw material to be constant by adjusting said supply of said carrier gas.

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- 26. (Amended) A method as claimed in claim 25, further comprising; filtering said raw material in the gas phase and supplying and hydrolyzing the filtered raw material in the gas phase.
- 27. (Amended) A method as claimed in claim 25, further comprising; controlling a flow rate of said raw material in the gas phase and supplying and hydrolyzing said flow rate controlled raw material in the gas phase.

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28. (Amended) A method as claimed in claim 25, wherein said supplying and hydrolyzing of said raw material occurs in a reaction vessel; and

said hydrolyzing includes cooling said reaction vessel by circulating cooling water around said reaction vessel.

29. (Amended) A method as claimed in claim 28, wherein said cooling water contains anticorrosive chemicals.

33. (Amended) A method as claimed in claim 32, wherein said cooling water contains inorganic nitride at a concentration substantially from 1 ppm to 10 ppm.

Please see the attached Appendix for changes made to effect the above claims.